



PTO/SB/08A (08-03)

Approved for use through 07/31/2008. OMB 0651-0031

U.S. Patent and Trademark Office; U.S. DEPARTMENT OF COMMERCE

Under the Paperwork Reduction Act of 1995, no persons are required to respond to a collection of information unless it contains a valid OMB control number.

Substitute for form 1449/PTO

**INFORMATION DISCLOSURE
STATEMENT BY APPLICANT**

(Use as many sheets as necessary)

Complete if Known

Application Number	10/616,662
Filing Date	July 10, 2003
First Named Inventor	Zhang, et al.
Art Unit	1751
Examiner Name	
Attorney Docket Number	06293P2 USA

Sheet

1

of

1

U. S. PATENT DOCUMENTS

Examiner Initials*	Cite No. ¹	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number-Kind Code ² (if known)			
<i>W</i>		US- 6,261,745	07-17-2001	Komano Hiroshi, et al.	
<i>W</i>		US- 5,977,041	11-02-1999	Honda Kenji	
<i>W</i>		US- 5,756,267	05-26-1998	Kobayashi Kesanao, et al.	
<i>W</i>		US- 5,650,543	07-22-1997	Medina Steven Wayne	
<i>W</i>		US- 4,833,067	05-23-1989	Asaumi Shingo, et al.	
<i>W</i>		US- 2002/016272	02-07-2002	Kakizawa Masahiko, et al.	
		US-			
		US-			
		US-			
		US-			
		US-			
		US-			

FOREIGN PATENT DOCUMENTS

Examiner Initials*	Cite No. ¹	Foreign Patent Document	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T ⁶
		Country Code ³ Number ⁴ Kind Code ⁵ (if known)				
<i>W</i>		EP 1 115 035 A	07-11-2001	Air Products and Chemicals, Inc.		✓
<i>W</i>		EP 1 389 745 A	02-18-2004	Air Products and Chemicals, Inc.		✓

Examiner
Signature*[Signature]*Date
Considered

9/3/2005

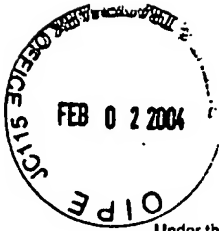
*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant. ¹Applicant's unique citation designation number (optional). ²See Kinds Codes of USPTO Patent Documents at www.uspto.gov or MPEP 901.04. ³Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). ⁴For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. ⁵Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST.16 if possible. ⁶Applicant is to place a check mark here if English language Translation is attached.

This collection of information is required by 37 CFR 1.97 and 1.98. The information is required to obtain or retain a benefit by the public which is to file (and by the USPTO to process) an application. Confidentiality is governed by 35 U.S.C. 122 and 37 CFR 1.14. This collection is estimated to take 2 hours to complete, including gathering, preparing, and submitting the completed application form to the USPTO. Time will vary depending upon the individual case. Any comments on the amount of time you require to complete this form and/or suggestions for reducing this burden, should be sent to the Chief Information Officer, U.S. Patent and Trademark Office, P.O. Box 1450, Alexandria, VA 22313-1450. DO NOT SEND FEES OR COMPLETED FORMS TO THIS ADDRESS. SEND TO:

Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.

If you need assistance in completing the form, call 1-800-PTO-9199 (1-800-788-9199) and select option 2.

PTO/SB/08A (08-03)



PTO/SB/08A (08-03)

Approved for use through 07/31/2006. OMB 0651-0031

U.S. Patent and Trademark Office; U.S. DEPARTMENT OF COMMERCE

Under the Paperwork Reduction Act of 1995, no persons are required to respond to a collection of information unless it contains a valid OMB control number.

Substitute for form 1449/PTO INFORMATION DISCLOSURE STATEMENT BY APPLICANT <i>(Use as many sheets as necessary)</i>				Complete if Known	
				Application Number	10/616,662
				Filing Date	10 July 2003
				First Named Inventor	Peng Zhang, et al.
				Art Unit	1751
Examiner Name					
Sheet	1	of	1	Attorney Docket Number	06293P2 USA

U. S. PATENT DOCUMENTS					
Examiner Initials*	Cite No. ¹	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number-Kind Code ² (if known)			
		US- 6,670,107	12/30/2003	J. F. Lachowski	
		US-			
		US-			
		US-			
		US-			
		US-			
		US-			
		US-			
		US-			
		US-			
		US-			
		US-			
		US-			
		US-			
		US-			

FOREIGN PATENT DOCUMENTS						
Examiner Initials*	Cite No. ¹	Foreign Patent Document	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T ⁶
		Country Code ³ Number ⁴ Kind Code ⁵ (if known)				

Examiner Signature		Date Considered	9/3/2005
-----------------------	--	--------------------	----------

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant. ¹Applicant's unique citation designation number (optional). ²See Kinds Codes of USPTO Patent Documents at www.uspto.gov or MPEP 901.04. ³Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). ⁴For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. ⁵Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST.16 if possible. ⁶Applicant is to place a check mark here if English language translation is attached.

This collection of information is required by 37 CFR 1.97 and 1.98. The information is required to obtain or retain a benefit by the public which is to file (and by the USPTO to process) an application. Confidentiality is governed by 35 U.S.C. 122 and 37 CFR 1.14. This collection is estimated to take 2 hours to complete, including gathering, preparing, and submitting the completed application form to the USPTO. Time will vary depending upon the individual case. Any comments on the amount of time you require to complete this form and/or suggestions for reducing this burden, should be sent to the Chief Information Officer, U.S. Patent and Trademark Office, P.O. Box 1450, Alexandria, VA 22313-1450. DO NOT SEND FEES OR COMPLETED FORMS TO THIS ADDRESS. SEND TO:

Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.

If you need assistance in completing the form, call 1-800-PTO-9199 (1-800-786-9199) and select option 2.

7/10/03

FORM PTO-1449 (Modified)	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY. DOCKET NO. 06293P2 USA	SERIAL NO.
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use several sheets if necessary)		APPLICANT Peng Zhang, et al.	
		FILING DATE	GROUP

(37 CFR 1.98(b))

U.S. PATENT DOCUMENTS

EXAM- INER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
<i>W</i>	0 0 5 5 6 6 0	5/9/2002	K. R. Lassila, et al.	568	616	10/11/2001
<i>W</i>	5 9 4 8 4 6 4	9/7/1999	F. M. Delnick	427	77	6/19/1996
<i>W</i>	5 9 7 7 0 4 1	11/2/1999	K. Honda	510	175	9/23/1997
<i>W</i>	6 1 5 2 1 4 8	11/28/2000	A. M. George, et al.	134	2	9/3/1998
<i>W</i>	6 3 1 3 1 8 2	11/6/2001	K. R. Lassila, et al.	516	204	5/4/1999
<i>W</i>	0 1 1 5 0 2 2	8/22/2002	S. A. Messick, et al.	430	311	2/21/2001

FOREIGN PATENT DOCUMENTS

EXAM- INER INITIAL	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
<i>W</i>	EP 1 1 1 5 0 3 5		Europe			X	
<i>W</i>	JP 95 1 4 2 3 4 9		Japan			X	
<i>W</i>	JP 96 0 0 8 1 6 3		Japan			X	
<i>W</i>	WO 0 0 0 3 3 0 6		World			X	
<i>W</i>	WO 0 2 2 3 5 9 8		World			X	
<i>W</i>	WO 8 7 0 3 3 8 7		World			X	
<i>W</i>	WO 9 9 1 5 6 0 9		World			X	
<i>W</i>	WO 9 9 6 0 0 8 3		World			X	
<i>W</i>	WO 9 9 6 0 4 4 8		World			X	

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

<i>W</i>	Domke, W. D., et al., "Pattern Collapse in High Aspect Ratio DUV and 193nm Resists," Proc. SPIE-Int. Soc. Opt. Eng. 3999, 313-321, 2000.
<i>W</i>	Cheung, C., et al., "A Study of a Single Closed Contact for 0.18 Micron Photolithography Process," Proc. SPIE-Int. Soc. Opt. Eng. 3998, 738-741, 2000.
<i>W</i>	S. Hien, et al., "Collapse behavior of single layer 193 and 157 nm resists: Use of surfactants in the rinse to realize the sub 130 nm nodes," Infineon Technologies, International SEMATECH, Center for Nano Technology, University of Wisconsin.
<i>W</i>	T. Tanaka, et al., "Mechanism of Resist Pattern Collapse During Development Process," Jpn. J. Appl. Phys. Vol. 32 (1993), pp. 6059-6064, Part 1, No. 12B.

EXAMINER <i>W</i>	DATE CONSIDERED 9/5/2005
-------------------	--------------------------

EXAMINER: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.